

Low Temperature Plasmas I)

- Irving Langmuir → Birth of plasma science, worked @ university initially, went to GE (Edisons company)
 - Realized noble gases last longer than others, coined the term plasma.
 - ⇒ Specifically started studying low temp plasma.

How to make them)

- Vacuum chamber, gas inside, applied electric field.
- Plasmas are collisional and radiative processes
 - Can look @ many different collision scenarios ($e^- + \text{Molecule}$, etc.)
 - The collisions yield many different results (ionization, etc), and get a result based on products from initial collision.
- Low Temp Plas → Non-equilibrium (Non-thermal)
 - ⇒ $T_e \gg T_i, T_n$ w/ $T_i \approx T_n$
 - Temps range from 350 K → 2,500 K

Langmuir Probe → Measure current, electron density.

PPPL has a remote glow discharge Experiment

Low-temp plasmas are used to etch holes, etc into silicon for use in semiconductors

- Can be expensive, electron beam lithography is expensive, why we wanted to do colloidal stuff w/ Dr. Pfeil.

LTP are easily generated @ low pressure, but its expensive.

- Push now for LTP formation @ atmospheric pressure, but they're unstable.
- Alternative is to decrease separation to μm 's ~~the~~ btwn anode/cathode.

Werner Siemens was studying plasmas. Huh! Ended up making O_3 generators using

Low Temperature Plasma I

- Generated O_3 can be used as bubble filters for water treatment applications.
- Atmospheric pressure plasma jets can interact w/ organic material!
- Microplasmas can be used ~~as~~ as antibacterial! They rupture the cell walls/membrane and kill microbes!
- Plasma medicine \Rightarrow Used to treat cancer (in naked mice)
- Can also treat teeth enamel for ~~teeth~~ brightness.
- Plasma treatment to basil seeds dramatically increases growth.
 - Changes the biochemistry!
- Treatment w/ APPJ on living tissue is a viable option for wound healing in pigs. Super Crazy!!

8/11 Low Temp Plasma II

- Low temp plasma industries, multiple multibillion dollar industries.
 - Semiconducting silicon chips \Rightarrow \$20B/year industry.
 - Thin films,
 - Electric propulsion \Rightarrow moving satellites in orbits \Rightarrow Plasma Thrusters
 - Nanomaterial syntheses \Rightarrow nanotubes, etc.
 - Plasma manufacturing (welding, cutting)
 - Plasma physics for electric grids + pulsed power (breakers and stuff)
- Semiconductor industry incentivized companies to open in USA and stay in USA
 - CHIPS for America Act.
 - American Companies invested \$40B in 2019.
 - Trying to stay competitive w/ China, Taiwan, etc.



Low Temperature Plasmas II)

- Plasma Sources for semiconductor manufacturing
 - Capacitively-coupled plasmas CCP.
 - Inductively-coupled discharges ICP.
 - Electron and Ion beams \rightarrow Generated by plasma processing system.
- Plasma needs to be considered using kinetic theory.
 - Need to recall that LTP are Not in thermal equilibrium ($T_e \gg T_i$)
 - Electron ion, photon energy distribution functions are all Not Maxwellian.

CCP + ICP Typical Parameters

- Density $n = 10^9 - 10^{13} \text{ /cm}^3$
- Gas pressure = few mTorr
- Small degree of ionization

Global Model \Rightarrow Particle balance determines T_e

- We can model electron temperature as a function of gas pressure.

Discharge modeling needs to be kinetic b/c e^- energy distrib. fcn is non Maxwellian

EEDF \Rightarrow Electron energy distribution function.

- e^- , e^- collisions make the electron energy a Maxwellian.
- \hookrightarrow Maybe b/c collisions is a kinetic process

Semiconductors \rightarrow Atomic Layer Deposition

\rightarrow Hard to control process, 

ALD lets you deposit one monolayer at a time, very smooth, very controllable.

Non Maxwellian DF's in LTP's Let us select the amount of cold electrons, hot electrons; gives us more control over the process.

Low Temperature III)

Optical Diagnostics to Characterize Plasma

- Ultrafast femtosecond lasers;

- TALIF, REMPI, FLEET, CARS, E-FISH

→ Send photon in, gets absorbed, look @ emitted photon to characterize the molecule involved.